

Process type factors	Gas <i>i</i>								
	CF <sub>4</sub>	C <sub>2</sub> F <sub>6</sub>	CHF <sub>3</sub>	CH <sub>2</sub> F <sub>2</sub>	C <sub>3</sub> F <sub>8</sub>	c-C <sub>4</sub> F <sub>8</sub>	NF <sub>3</sub> remote	NF <sub>3</sub>	SF <sub>6</sub>
Etch 1-U <sub>1</sub>	0.6	N/A	0.2	N/A	N/A	0.1	N/A	N/A	0.3
Etch PCF <sub>4</sub>	N/A	N/A	0.07	N/A	N/A	0.009	N/A	N/A	N/A
Etch PCHF <sub>3</sub>	N/A	N/A	N/A	N/A	N/A	0.02	N/A	N/A	N/A
Etch PC <sub>2</sub> F <sub>6</sub>	N/A	N/A	0.05	N/A	N/A	N/A	N/A	N/A	N/A
CVD 1-U <sub>1</sub>	N/A	N/A	N/A	N/A	N/A	N/A	0.03	0.3	0.9